

Selective-area deposition of TiO_2 thin film using organic
thin-layer and metal organic chemical vapor deposition
(MOCVD)

미세접촉인쇄와 금속-유기 화학증착법을 이용한
산화티타늄 박막의 형상화

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Patterned thin films of TiO_2 were deposited by metal organic chemical vapor deposition (MOCVD) onto Si substrates and surface modification by self-assembled monolayer. The organic thin film of self-assembled monolayer (SAM) is created by the microcontact printing method and utilized as resister film to protect the deposition of TiO_2 . Selective deposition of TiO_2 thin film with 1000Å thickness has been successfully carried out at the temperature range of 300 to 350 °C.